



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

KOZAWA et al.

Attorney Docket No: 100021-00065

Application No. 10/005,347

Art Unit: 1712

Filed: December 7, 2001

Examiner: K. Peng

For: SILICON-CONTAINING POLYMER, PROCESS FOR ITS PRODUCTION,
RESIST COPOSITION EMPLOYING IT, PATTERN-FORMING METHOD AND
ELECTRONIC DEVICE FABRICATION METHOD

AMENDMENT UNDER 37 C.F.R. § 1.111

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

August 3, 2005

Sir:

In reply to the Office Action dated May 25, 2005, Applicants respectfully request reconsideration of the above-identified application in view of the following amendments and remarks: